

L Number	Hits	Search Text	DB	Time stamp
1	9010	((Chemical adj mechanical adj polish\$3) or CMP or planariz\$5) and (slurry or composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/13 14:28
8	3477	(((Chemical adj mechanical adj polish\$3) or CMP or planariz\$5) and (slurry or composition)) and (((Chemical adj mechanical adj polish\$3) or CMP or planariz\$5)same (metal\$1 or tungsten))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/13 14:30
15	27	((((Chemical adj mechanical adj polish\$3) or CMP or planariz\$5) and (slurry or composition)) and (((Chemical adj mechanical adj polish\$3) or CMP or planariz\$5)same (metal\$1 or tungsten))) and (ammonium adj nitrate\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/13 14:31